



Amorphous Oxide Semiconductor-Based Memristive Devices and Thin-Film Transistors

Guest Editors:

Dr. Asal Kiazadeh

Department of Materials Science,
Faculty of Science and
Technology, Universidade NOVA
de Lis-boa and
CEMOP/UNINOVA, Campus de
Caparica, 2829-516 Caparica,
Portugal

Dr. Emanuel Carlos

i3N/CENIMAT, Department of
Materials Science, Faculty of
Science and Technology,
Universidade Nova de Lisboa,
2829-516 Caparica, Portugal

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Message from the Guest Editors

We invite researchers and scientists to showcase their work in this Special Issue with research papers and review articles that focus on trends in AOS-based memristors, thin-film transistors, diodes and integration strategies, modelling, and simulation, from fundamental research to applications.

- Solution-based technology (coating and printing techniques)
- AOS memristive devices and systems
- neuromorphic computing with AOS-based memristors
- pattern recognition based on AOS memristors
- integration of AOS memristors with TFTs
- system-on-panel applications
- novel circuits on AOS-based memristors
- modeling and simulation of AOS processes for memristive devices
- circuit models and simulation of AOS memristors and TFTs
- resistive RAM based on AOS materials





Editor-in-Chief

Message from the Editor-in-Chief

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Micromachines Editorial Office
MDPI, St. Alban-Anlage 66
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